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PRELIMINARY AMENDMENT

Serial Number: Unknown Filing Date: Herewith

Title: IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

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- 44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.
- 45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.
- 46. The method of claim 1 wherein the film comprises a moldable polymer.
- 47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.
- 48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.
- 49. The method of claim 48 wherein the film is a sol.
- 50. The method of claim 1 wherein the film comprises microfibers.
- 51. The method of claim 1 wherein the film comprises a multilayer of films.
- 52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.
- 53. The method of claim 1 wherein the substrate comprises a single crystal material.
- 54. The method of claim 1 where in the substrate comprises an amorphous material.

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- 55. The method of claim 1 where the substrate comprises a composite material.
- <u>56.</u> The method of claim 1 where the substrate comprises a multilayer substrate.
- 57. The method of claim 1 wherein the pattern in the mask material is transferred to one layer of a multilayer film.
- 58. The method of claim 1 wherein the pattern in the mask material is more than one layer of a multilayer film.
- 59. The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is used as a mask to pattern the underlying layers in the multilayer film.

### **CONCLUSION**

Claims 2-41 have been cancelled without prejudice, and new claims 42-59 have been added. Claims 1 and 42-59 are pending in this application.

The Examiner is invited to call Applicant's attorney (612-359-3261) if there are any questions concerning this application.

Respectfully submitted,

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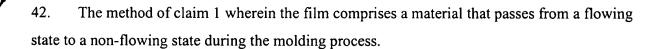
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### **Clean Version of Pending Claims**

# IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

Applicant: Stephen Y. Chou Serial No.:



- 43. The method of claim 42 wherein the film comprises a thermoplastic, hardenable or curable material.
- 44. The method of claim 42 wherein the material passes from a flowing state to a non-flowing state upon change of temperature, pressure, polymerization, irradiation or charging.
- 45. The method of claim 1 wherein the film comprises a film layer selected from the group consisting of: polymer film, latex film, viscous polymer coating, composite coating, fusible powder coating, adherent powder coating or fusible powder coating.
- 46. The method of claim 1 wherein the film comprises a moldable polymer.
- 47. The method of claim 1 wherein the film comprises a moldable polymer selected from the group consisting of: acrylates, methacrylates, polycarbonates, polyvinyl resins, polyimides, polyurethanes, polysiloxanes, polyesters and polyethers.
- 48. The method of claim 1 wherein the film comprises metal oxides, metal halides, semimetal oxides or semimetal halides.



- 49. The method of claim 48 wherein the film is a sol.
- 50. The method of claim 1 wherein the film comprises microfibers.
- 51. The method of claim 1 wherein the film comprises a multilayer of films.
- 52. The method of claim 1 wherein the substrate comprises a semiconductor, insulator or metal.
- 53. The method of claim 1 wherein the substrate comprises a single crystal material.
- 54. The method of claim 1 where in the substrate comprises an amorphous material.
- 55. The method of claim 1 where the substrate comprises a composite material.
- 56. The method of claim 1 where the substrate comprises a multilayer substrate.
- 57. The method of claim 1 wherein the pattern in the mask material is transferred to one layer of a multilayer film.
- 58. The method of claim 1 wherein the pattern in the mask material is more than one layer of a multilayer film.
- 59. The method of claim 1 wherein the pattern transferred to one layer of a multilayer film is used as a mask to pattern the underlying layers in the multilayer film.

# Clean Version of Specification Paragraphs

# IMPROVED RELEASE SURFACES, PARTICULARLY FOR USE IN NANOIMPRINT LITHOGRAPHY

Applicant: Stephen Y. Chou Serial No.:

## **RELATED APPLICATIONS**

This application is a divisional of U.S. Patent Application Serial No. 09/107,006, filed June 30, 1998, which claims priority to U.S. Patent No. 6,772,905, issued June 30, 1998.